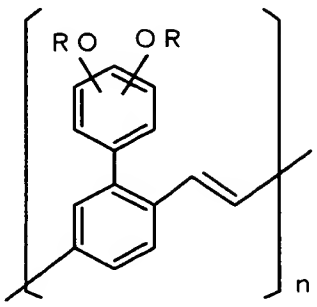
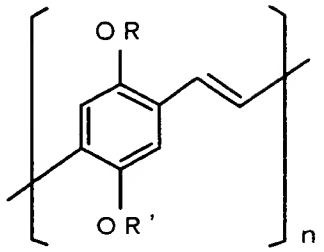
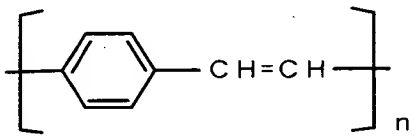
Compound 1



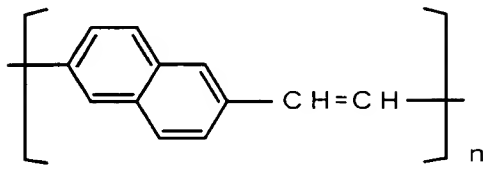
Compound 2



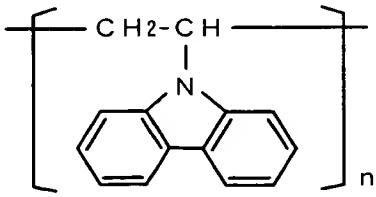
Compound 3



Compound 4



Compound 5



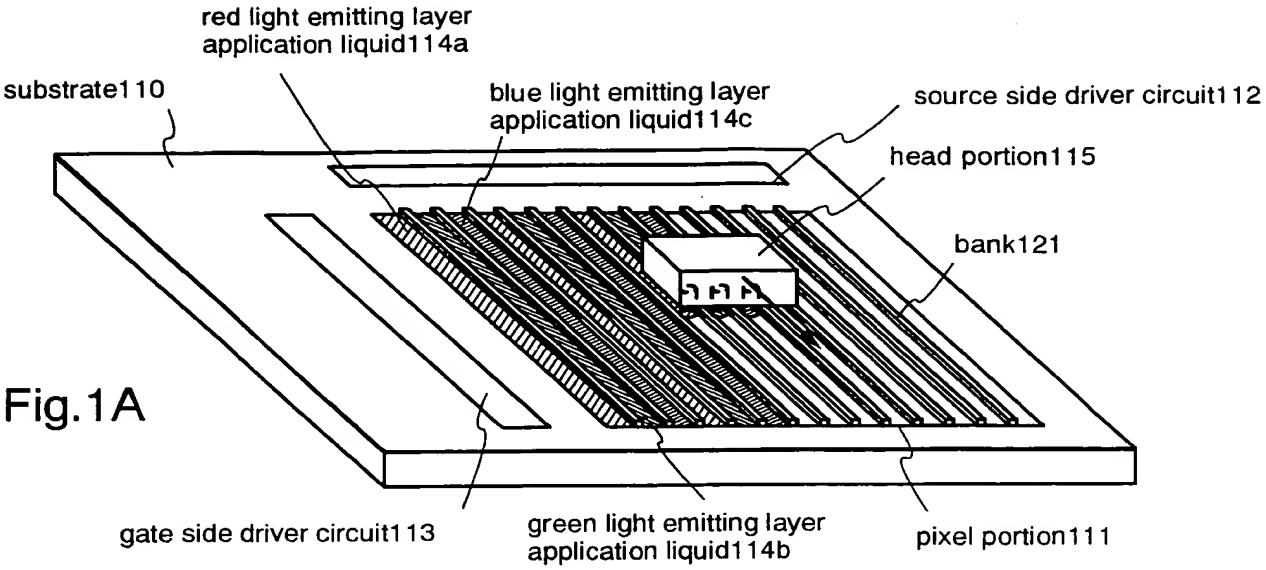


Fig.1A

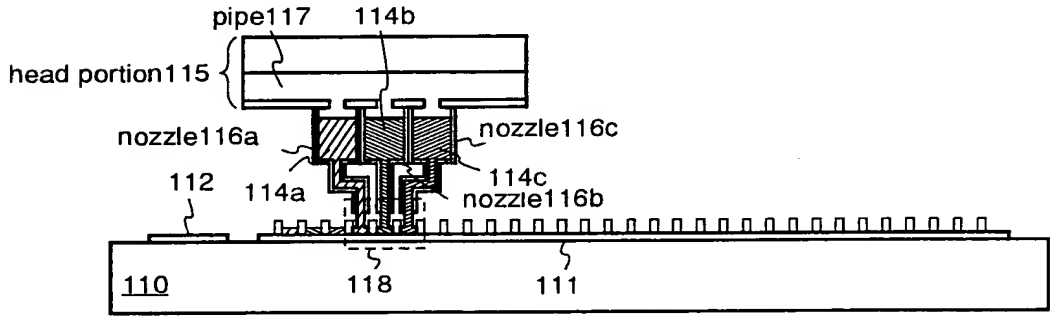


Fig.1B

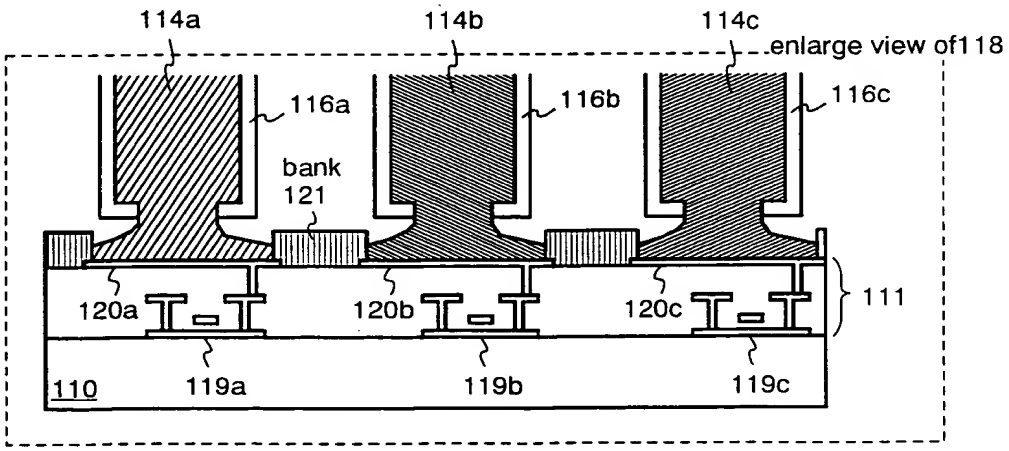
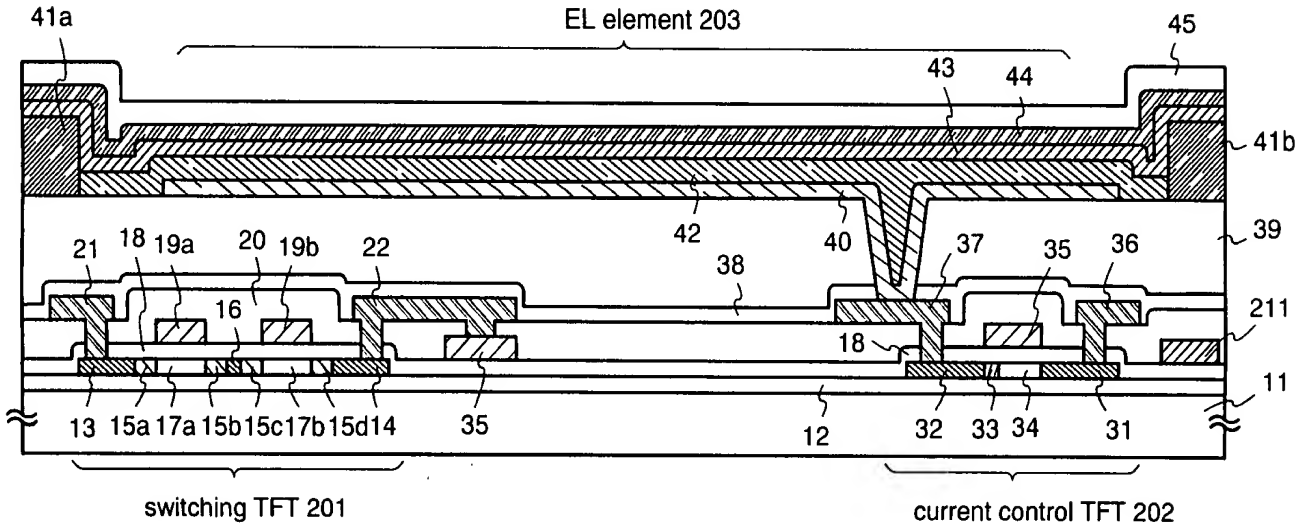


Fig.1C



11:substrate 12:base film 13:source region 14:drain region 15a-15d:LDD regions
16:high concentration impurity regions 7a,17b:channel forming region
18:gate insulating film 19a,19b:gate electrodes 20:first interlayer insulating film
21:source wiring 22:drain wiring 23:gate electrode 31:source region 32:drain region
33:LDD region 34:channel forming region 35:gate electrode 36:source wiring
37:drain wiring 38:first passivation film 39:second interlayer insulating film
40:pixel electrode(cathod) 41:bank 42:light emitting layer 43:hole injection layer
44:anode 45:second interlayer insulating film

Fig.2

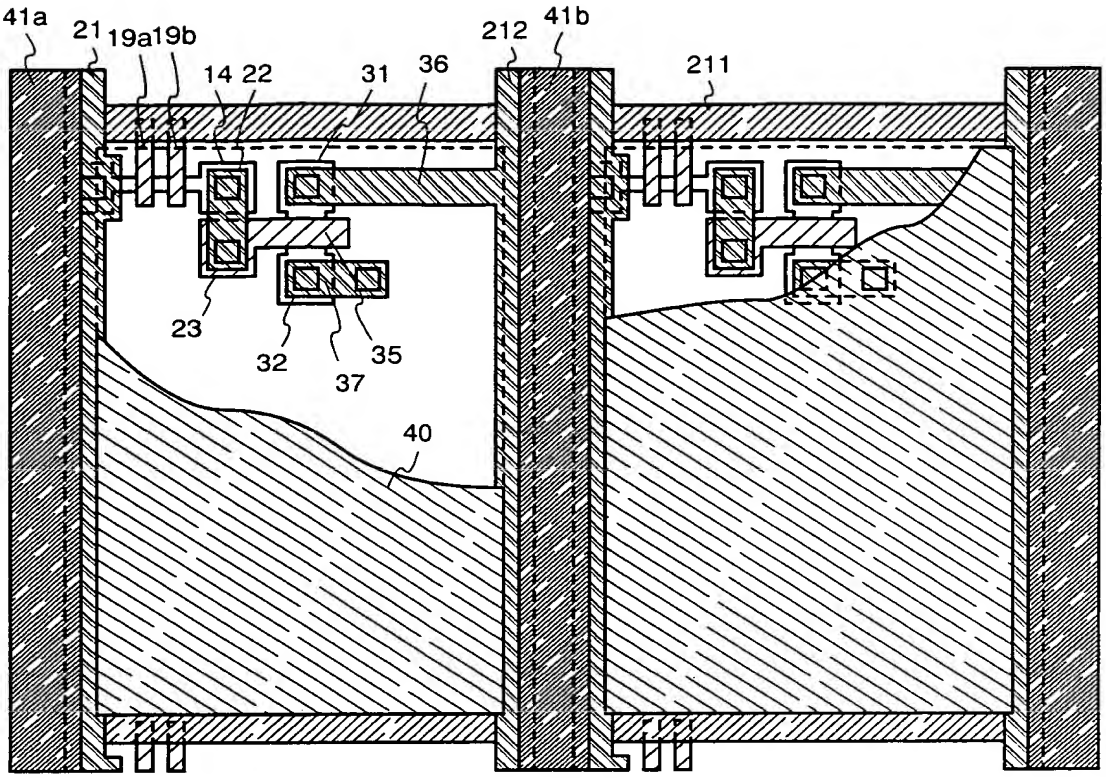

41a
21
19a
19b
14
22
31
36
212
41b
211
23
32
37
35
40

Fig.3A

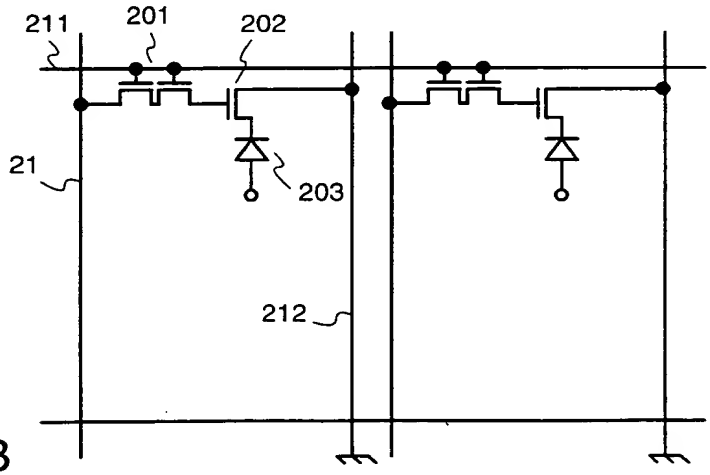

211
201
202
21
203
212

Fig.3B

Fig.4A

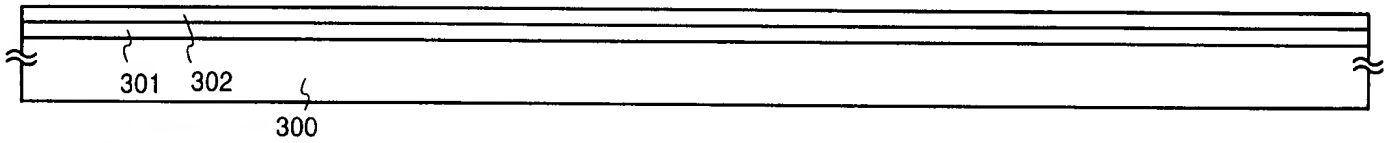


Fig.4B

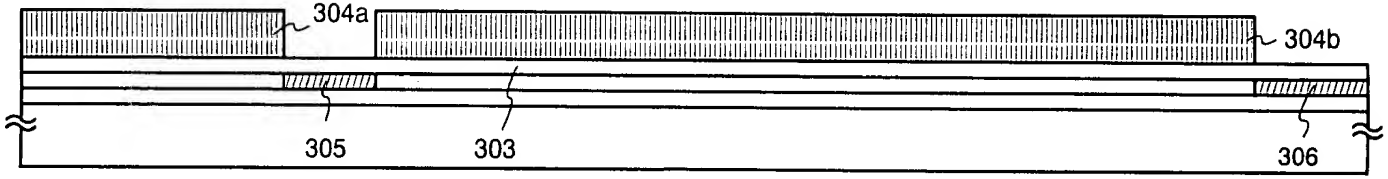


Fig.4C

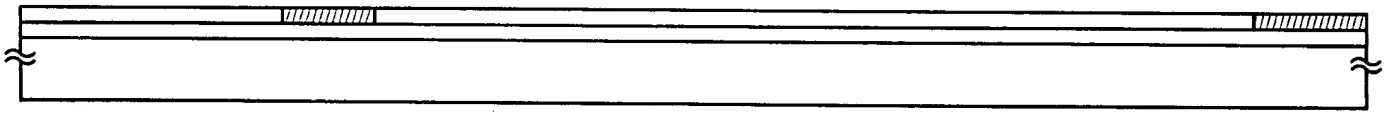


Fig.4D

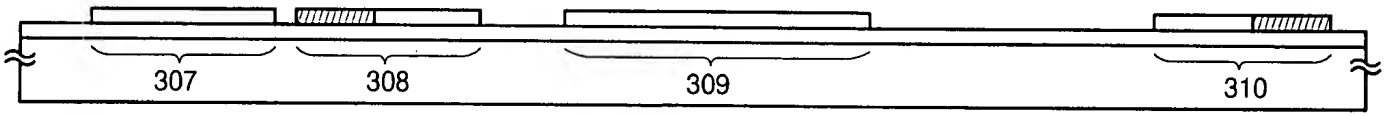
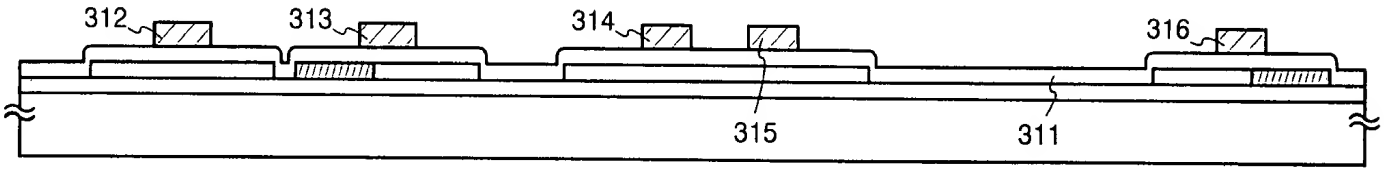


Fig.4E



300:glass substrate 301base film 302polysilion film 303:protective film 304a-304b resisit mask
305,306:n-type inpurity regions 307-310:active layers 311:gate insulating film 312-316:gate electodes

Fig.5A

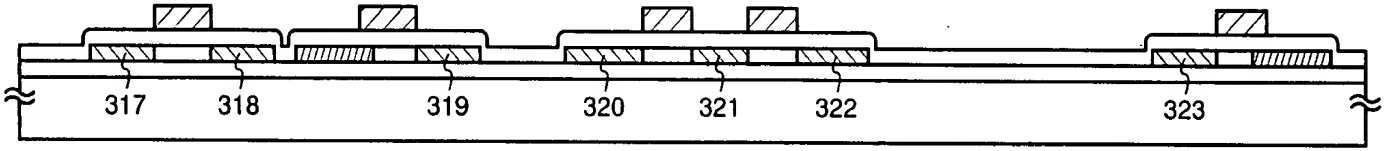


Fig.5B

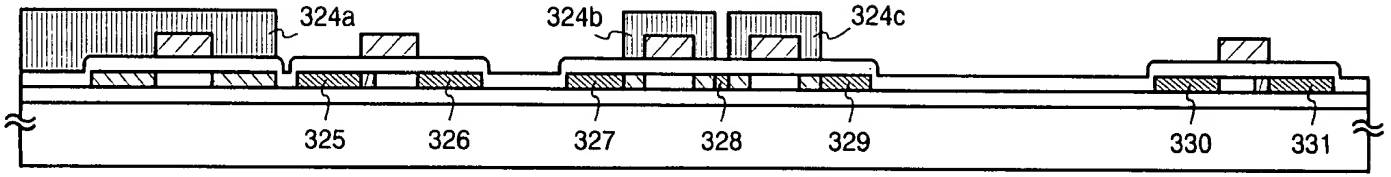


Fig.5C

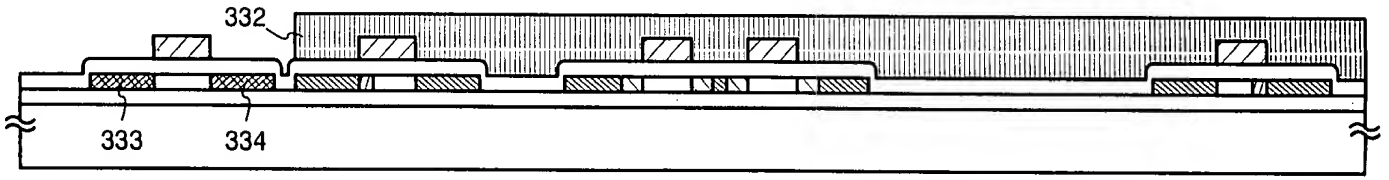
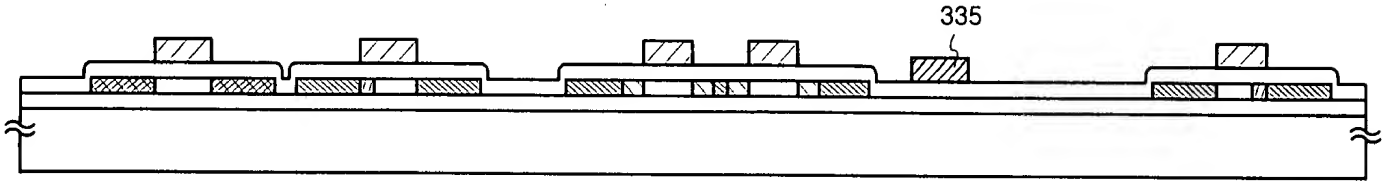


Fig.5D



317-323:n-type impurity regions 324a-324c,332:resisit mask 325-331:n-type impurity regions 333,334:p-type impurity regions 335:gate wiring

Fig.6A

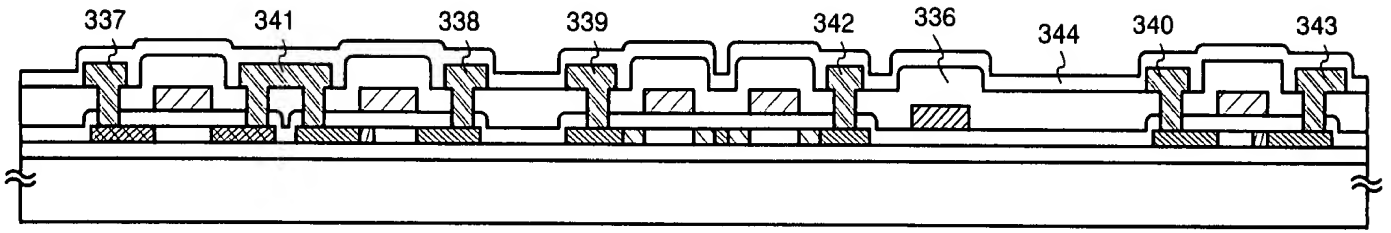


Fig.6B

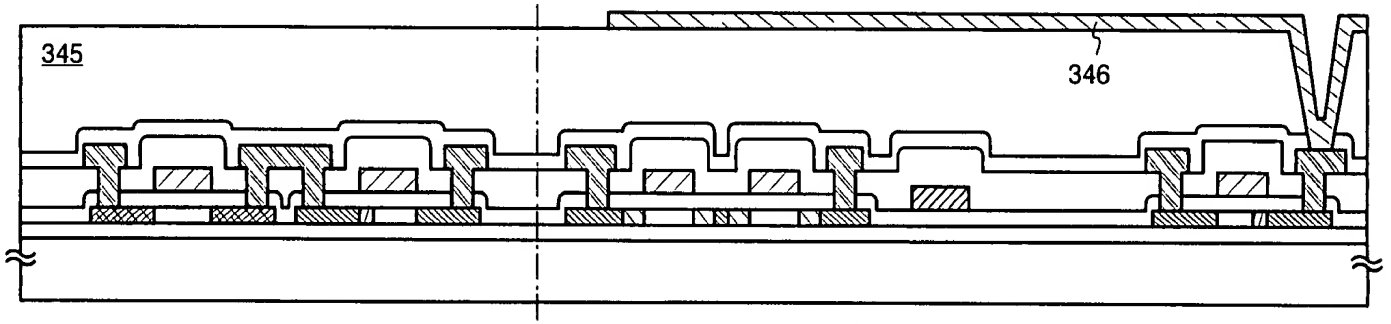
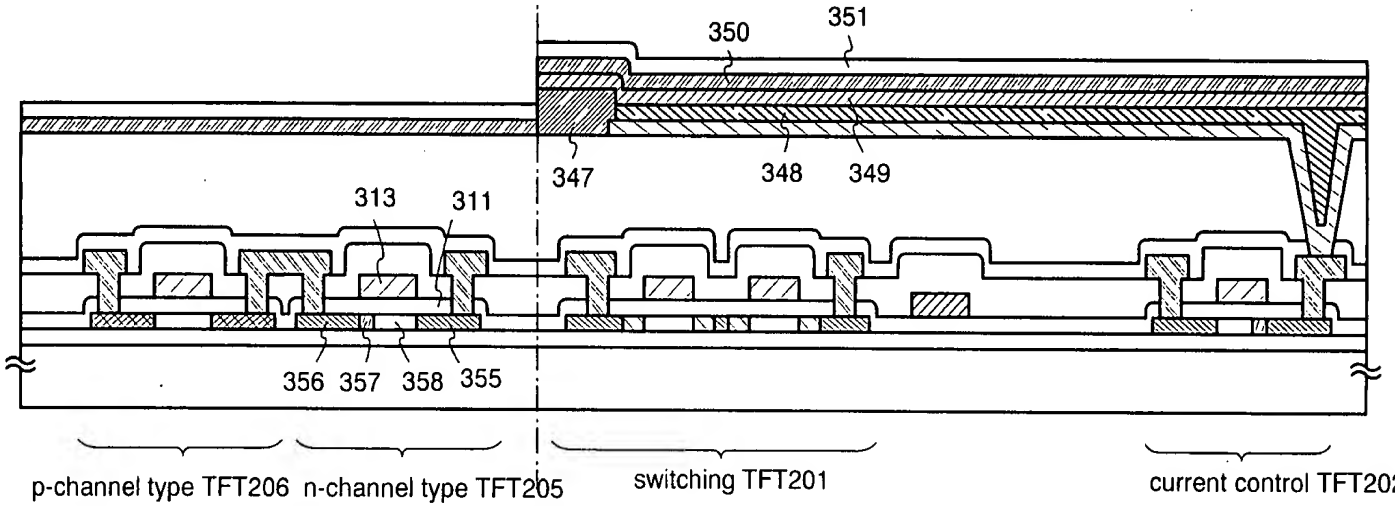
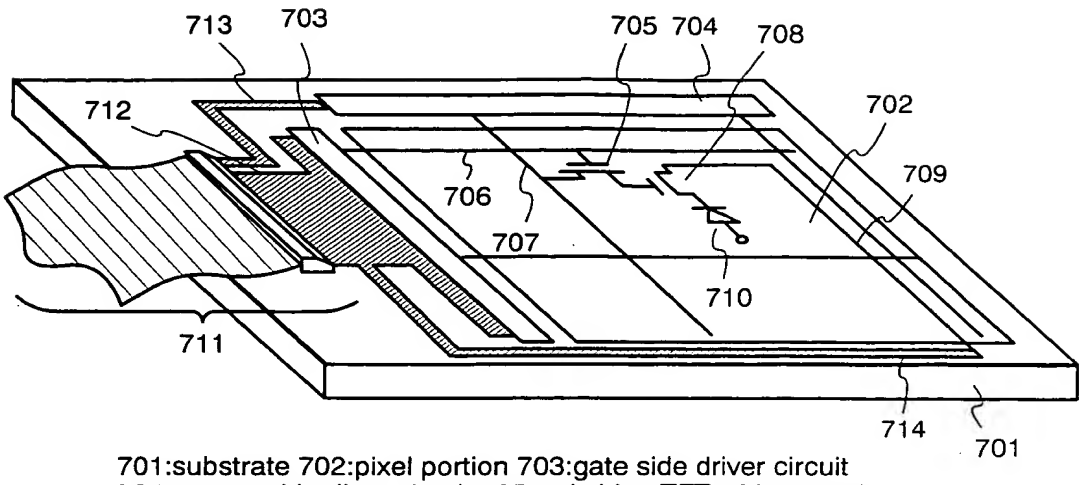


Fig.6C



336:first interlayer insulating film 337-340:source wiring 341-343:drain wiring
344:first passivation film 345:second interlayer insulating film 346:pixel electrode(cathod)
347:bank 348:light emitting layer 349:hole injection layer 350:anode 351:second passivation film



701:substrate 702:pixel portion 703:gate side driver circuit
704:source side diver circuit 705:switching TFT 706:gate wiring
707:source wiring 708:current control TFT 709:current supply line
710:EL element 711:FPC 712-714:connection wiring

Fig.7

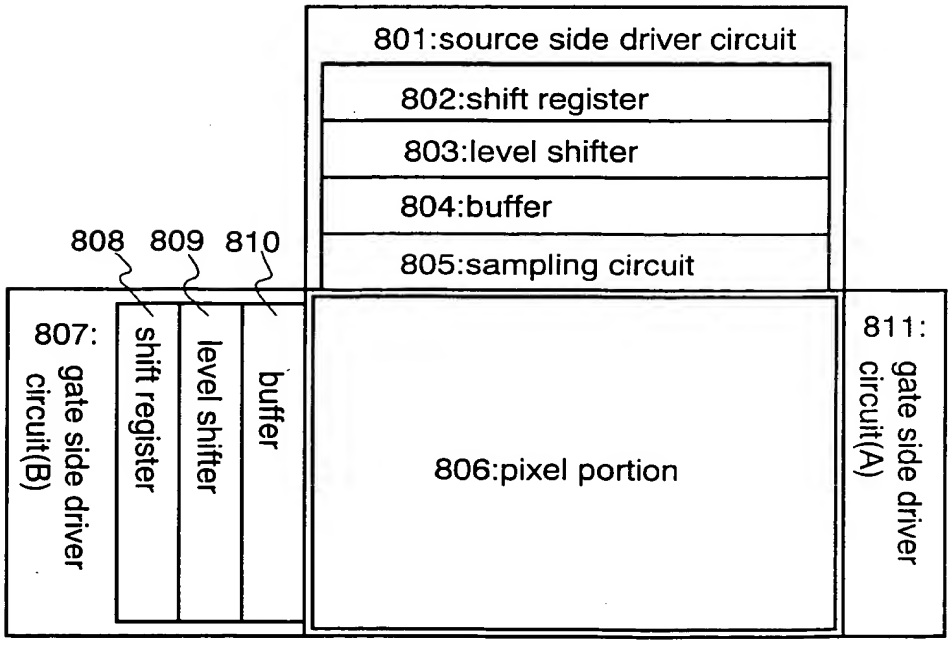


Fig.8

Fig.9

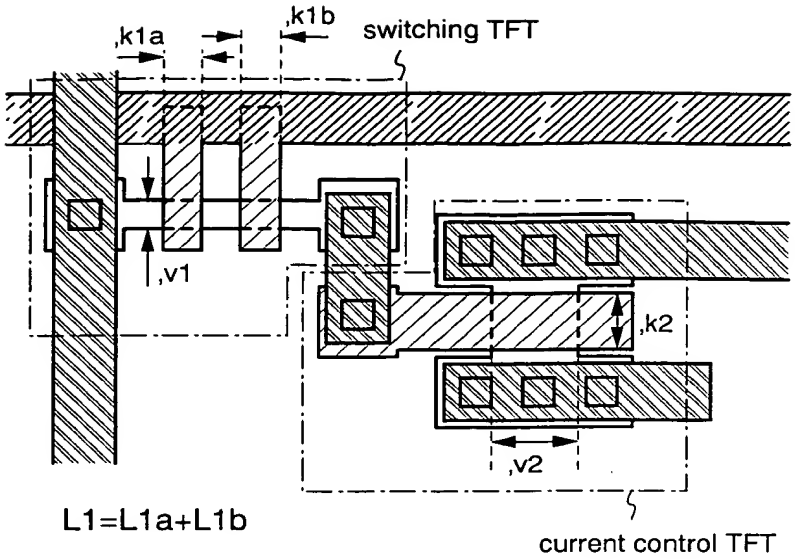
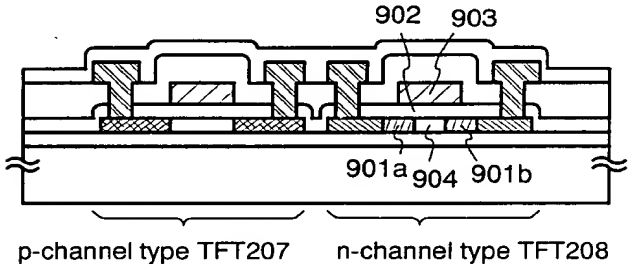

,k1a
,k1b
switching TFT
,v1
,k2
,v2
L1=L1a+L1b
current control TFT

Fig.10


902
903
901a
904
901b
p-channel type TFT207
n-channel type TFT208

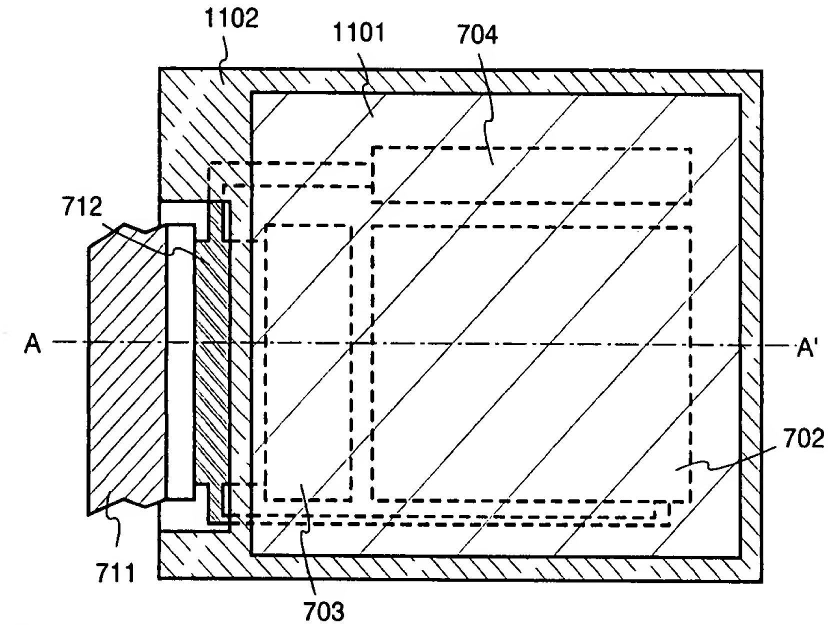


Fig.11A

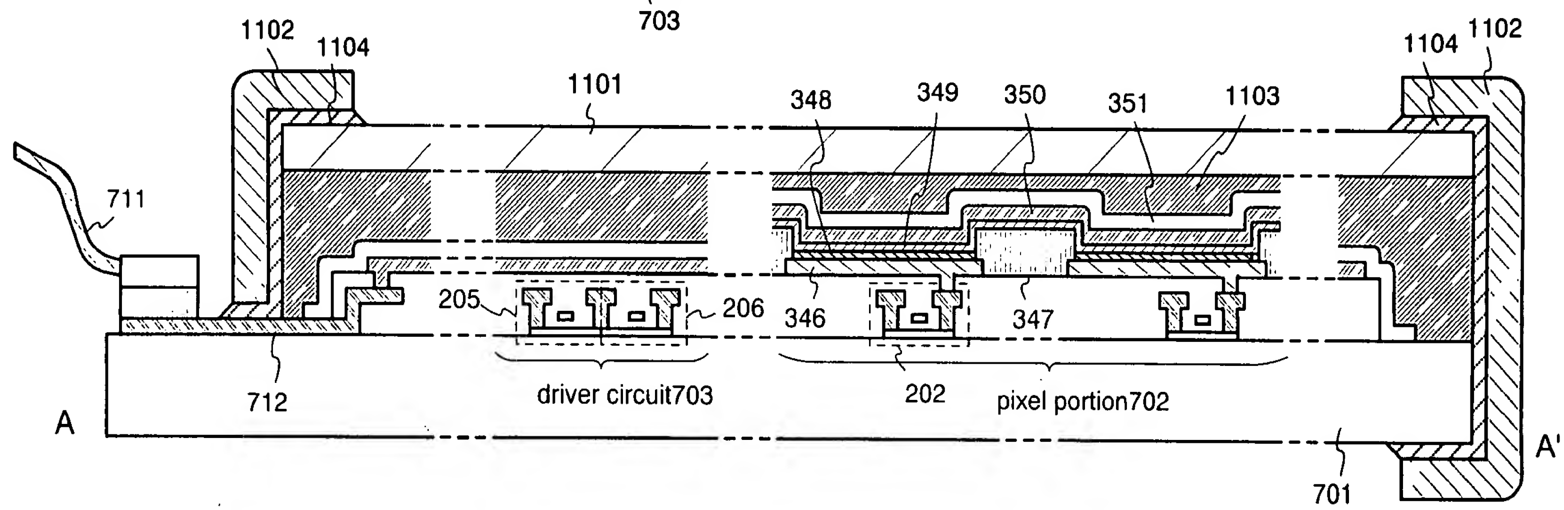


Fig.11B

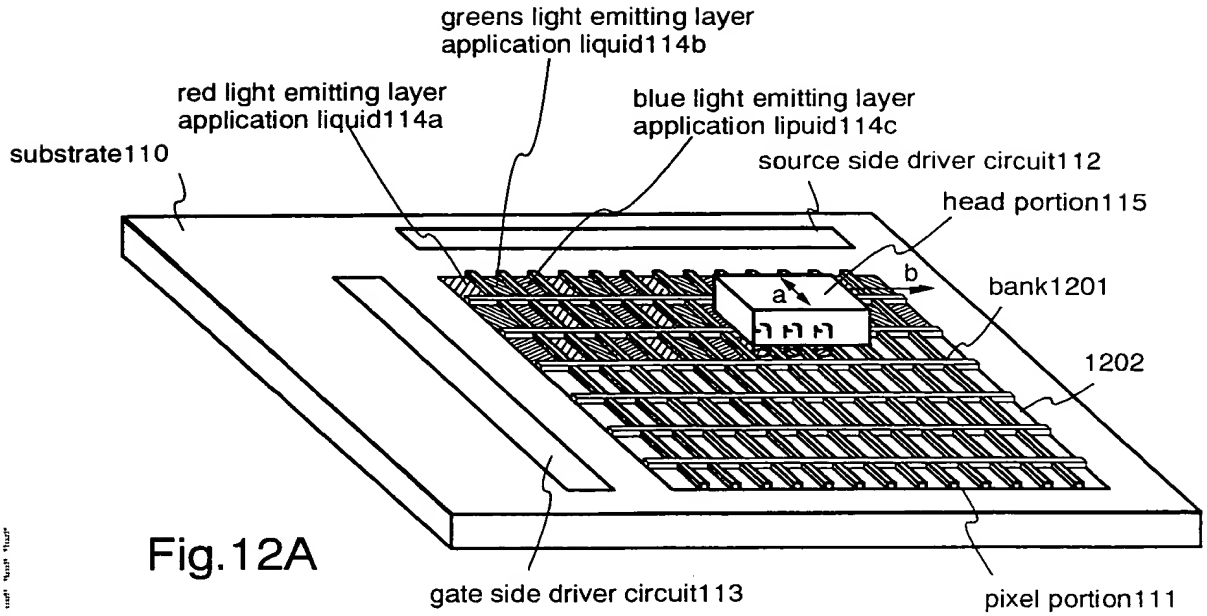


Fig.12A

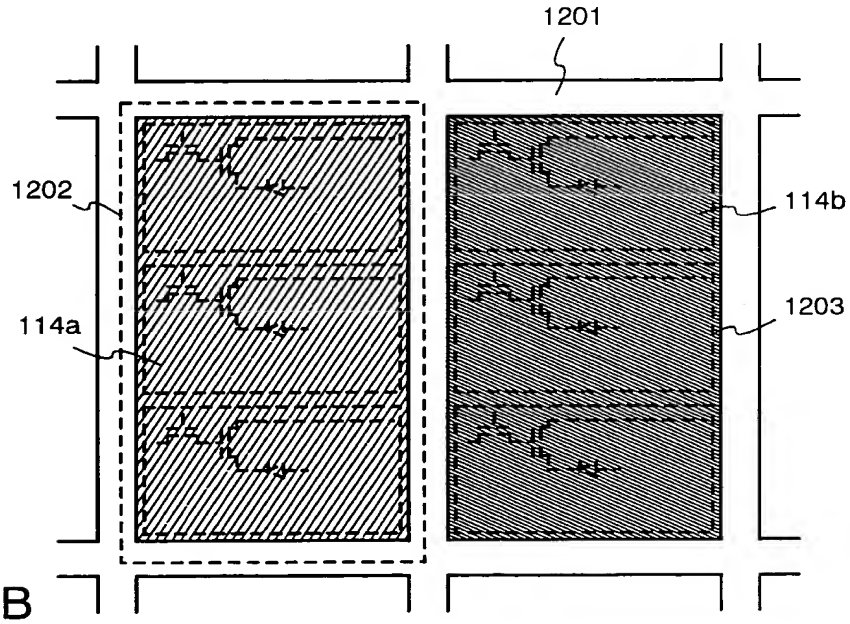


Fig.12B

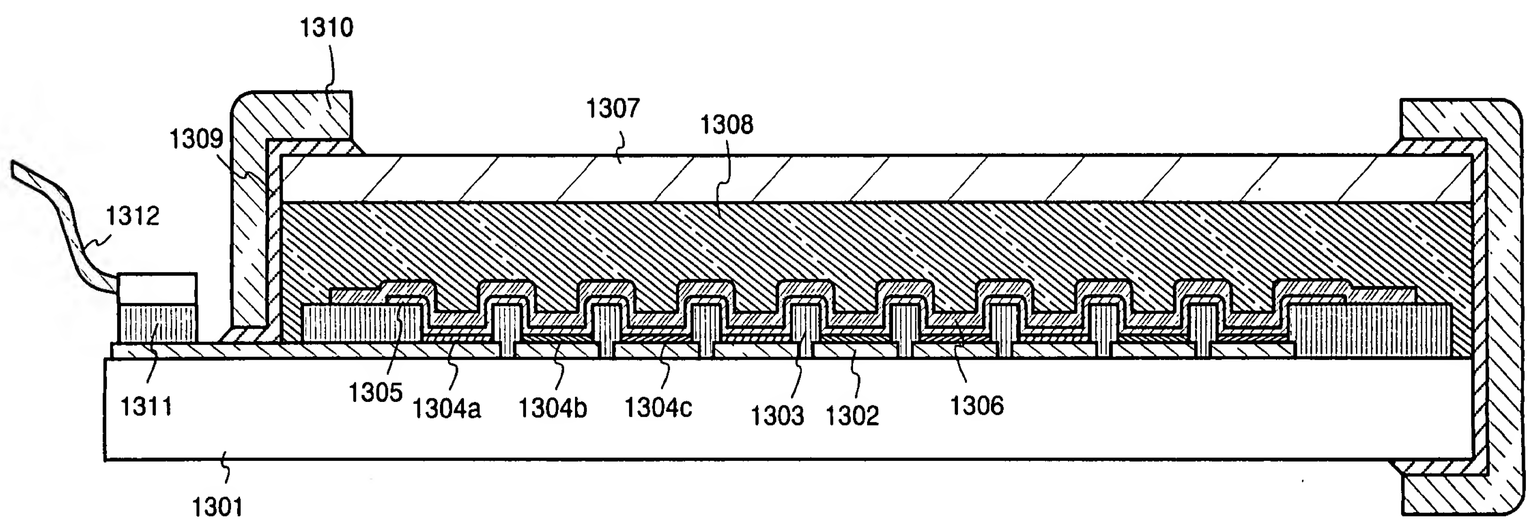

1310
1307
1308
1309
1312
1311
1305
1304a
1304b
1304c
1303
1302
1306
1301

Fig.13

Fig.14A

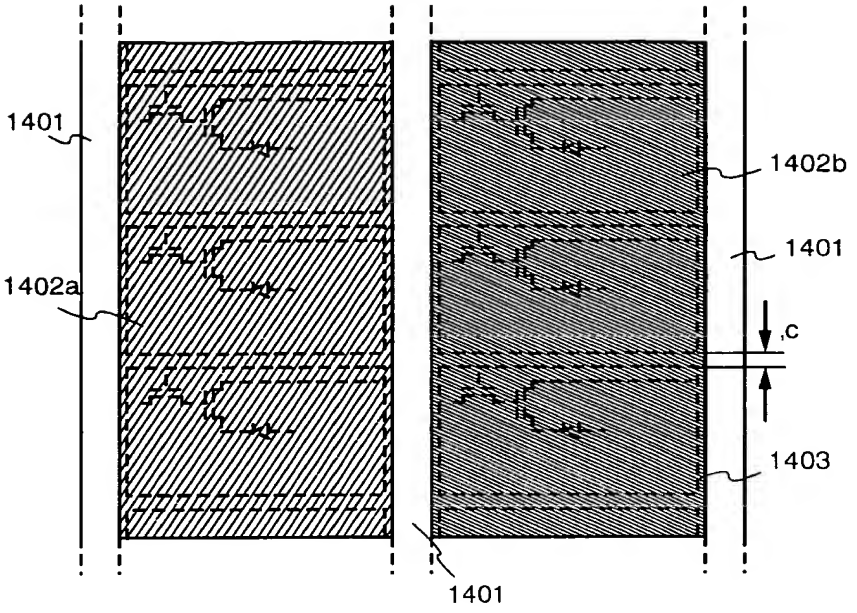
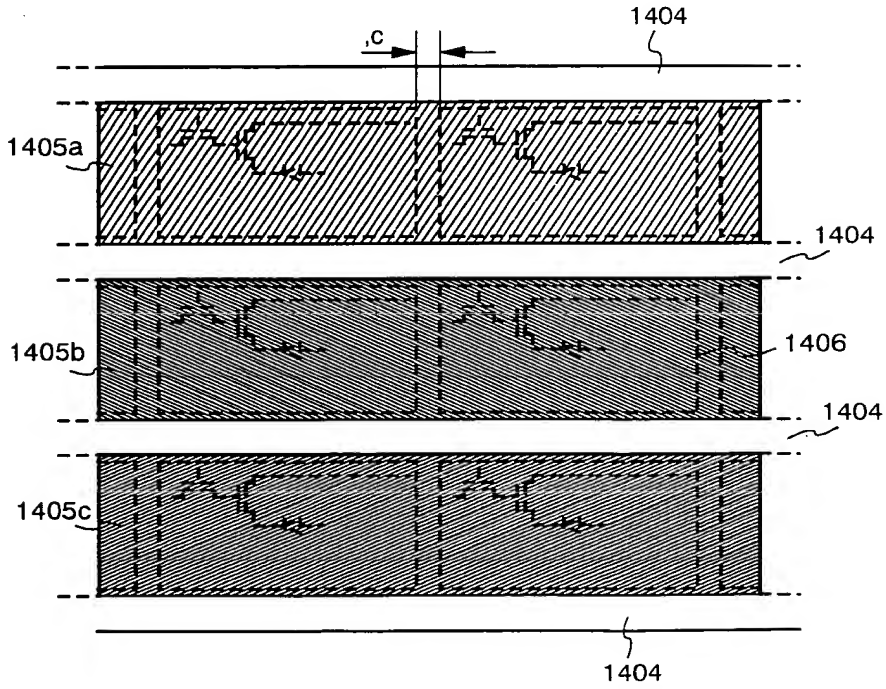


Fig.14B



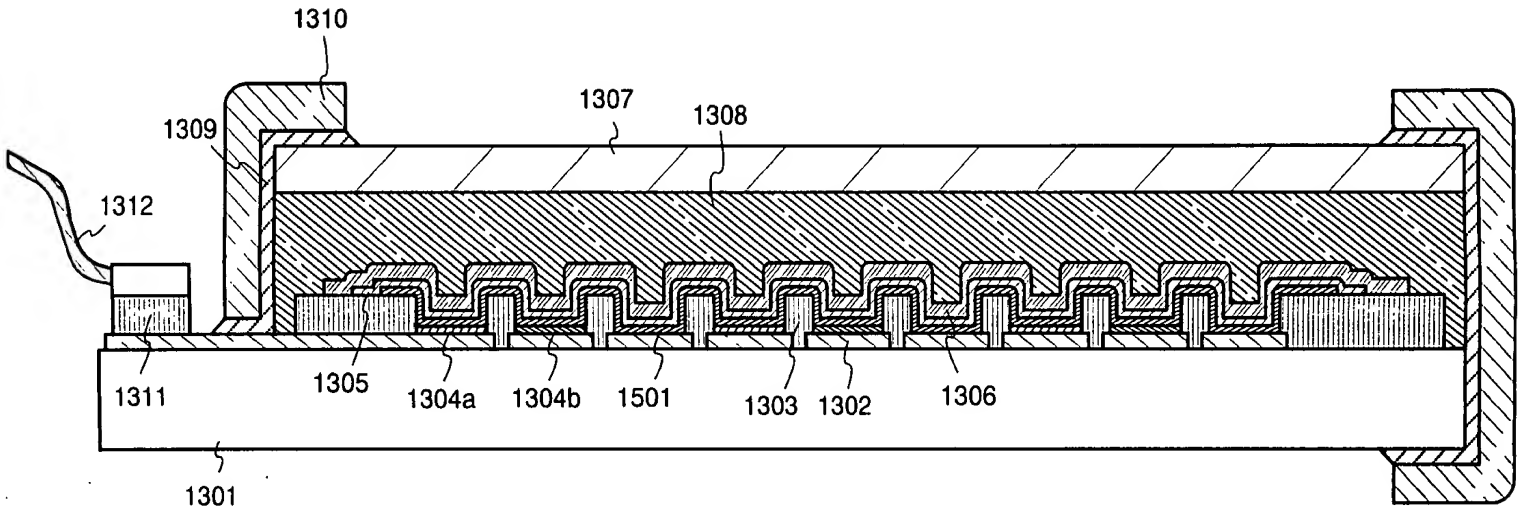

1310
1307
1308
1309
1312
1311
1305
1304a
1304b
1501
1303
1302
1306
1301

Fig.15

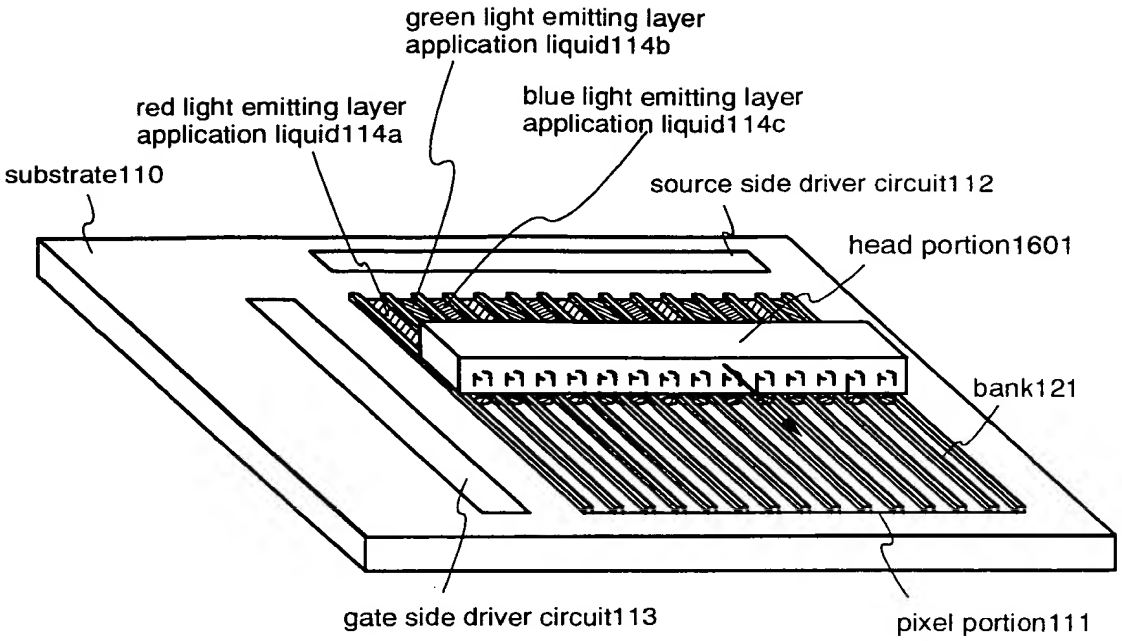

green light emitting layer
application liquid114b
red light emitting layer
application liquid114a
blue light emitting layer
application liquid114c
substrate110
source side driver circuit112
head portion1601
bank121
gate side driver circuit113
pixel portion111

Fig.16

Fig.17A

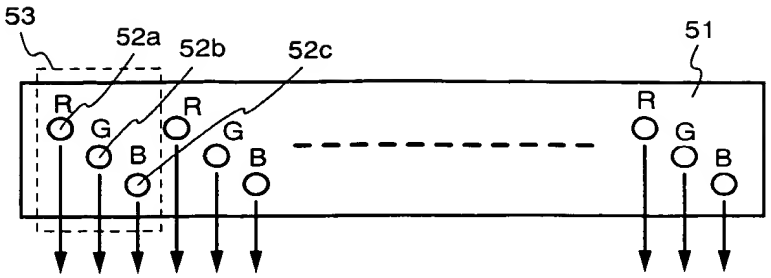


Fig.17B

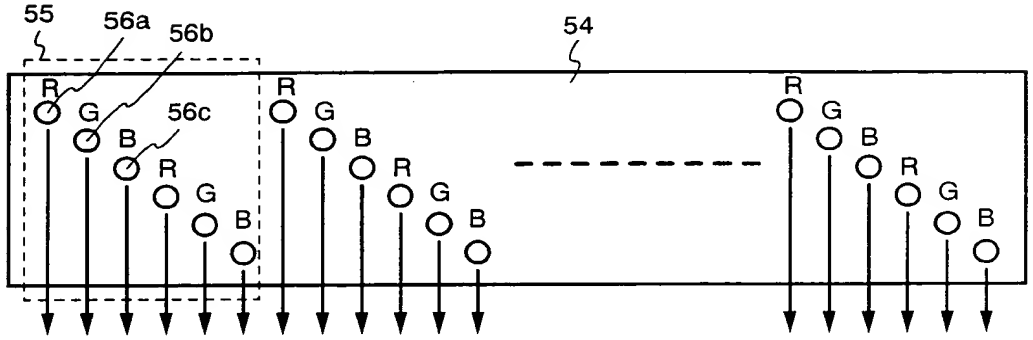
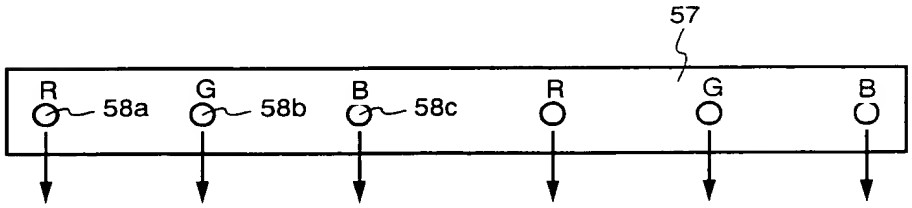


Fig.17C



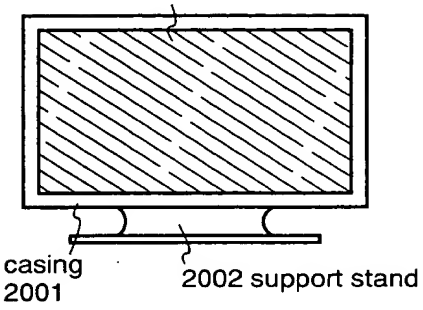


Fig.18A

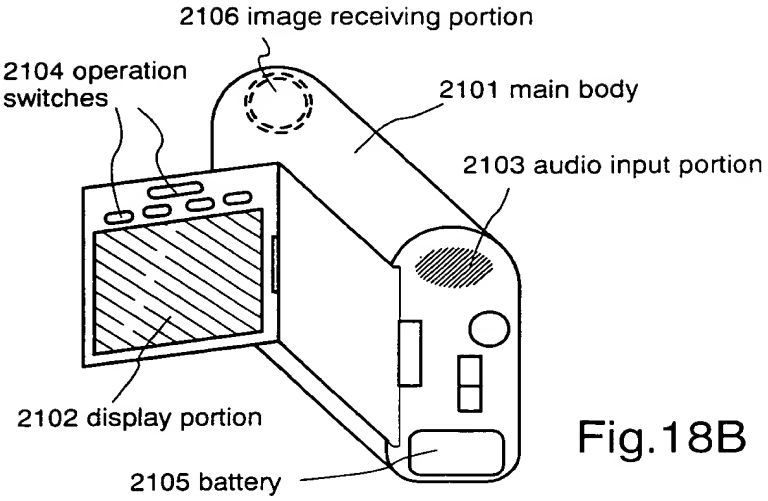


Fig.18B

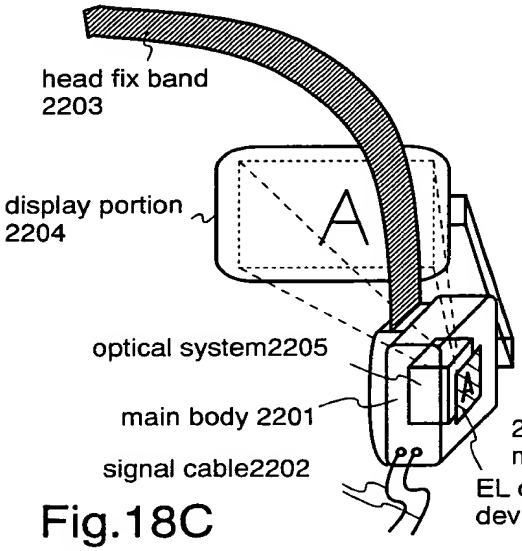


Fig.18C

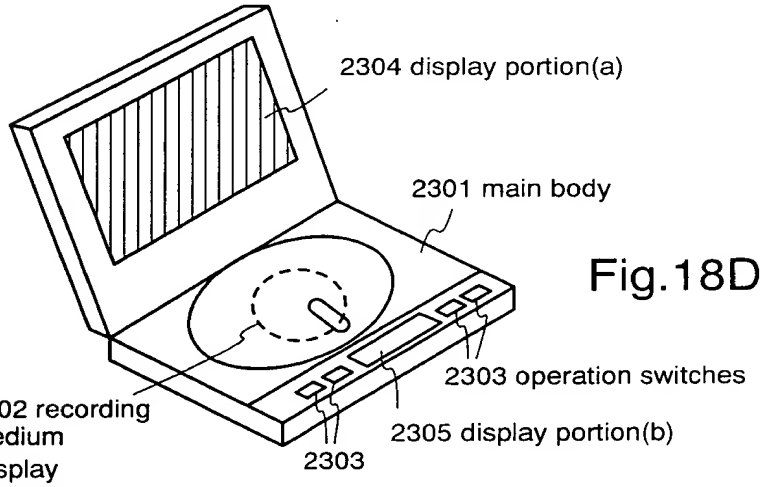


Fig.18D

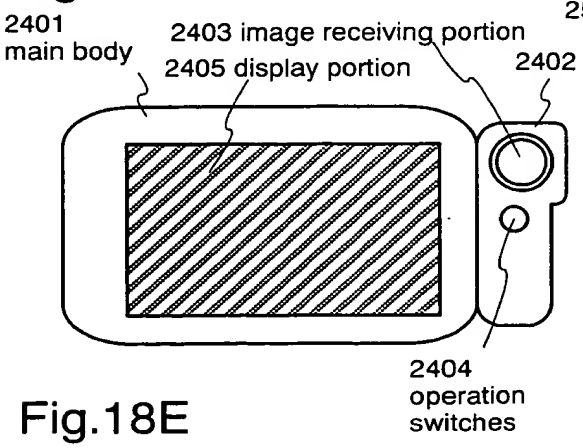


Fig.18E

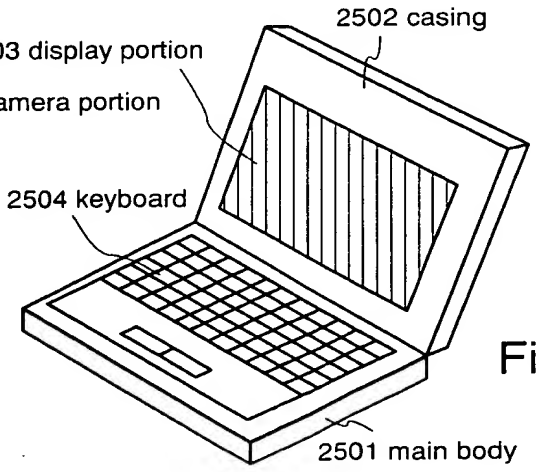


Fig.18F

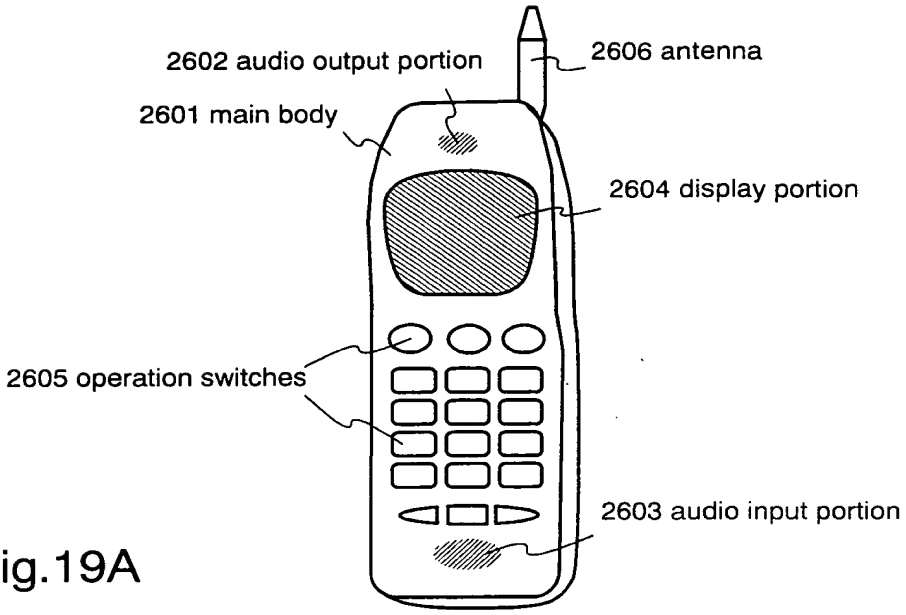


Fig.19A

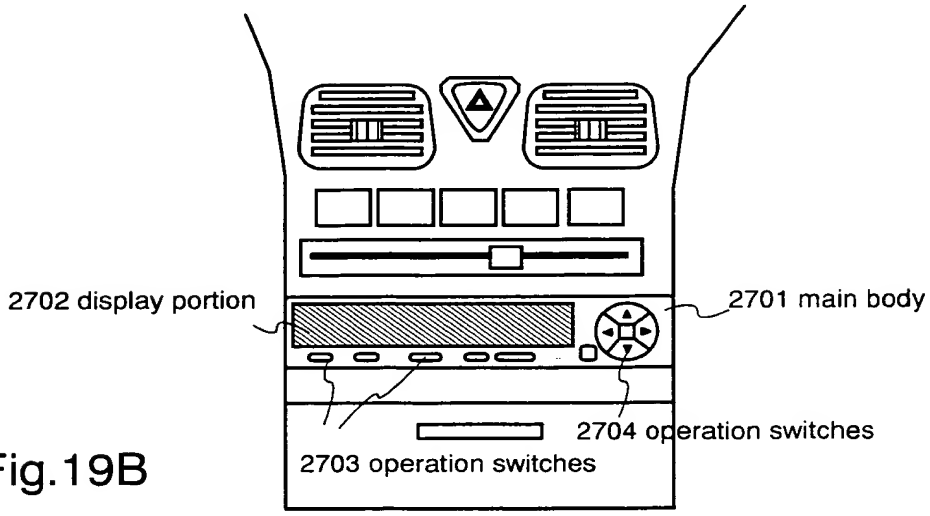


Fig.19B

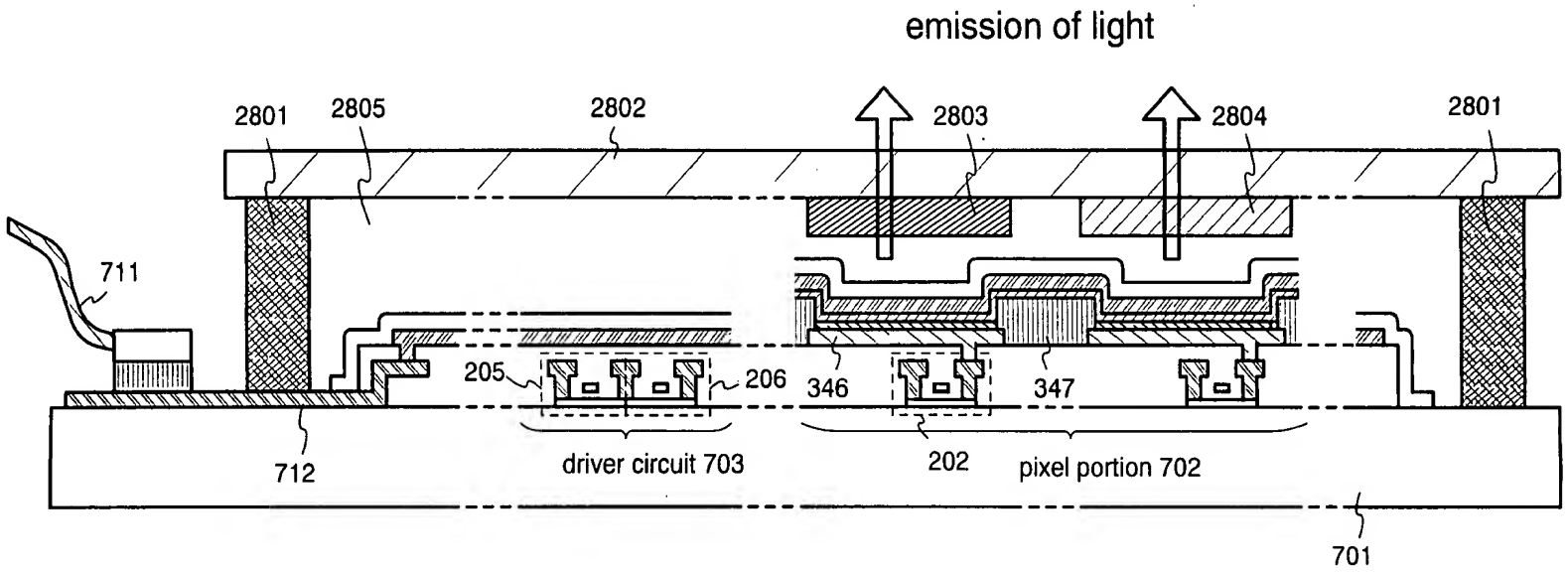

emission of light
2801
2805
2802
2803
2804
2801
711
205
206
346
347
712
driver circuit 703
202
pixel portion 702
701

Fig.20

Fig.21A

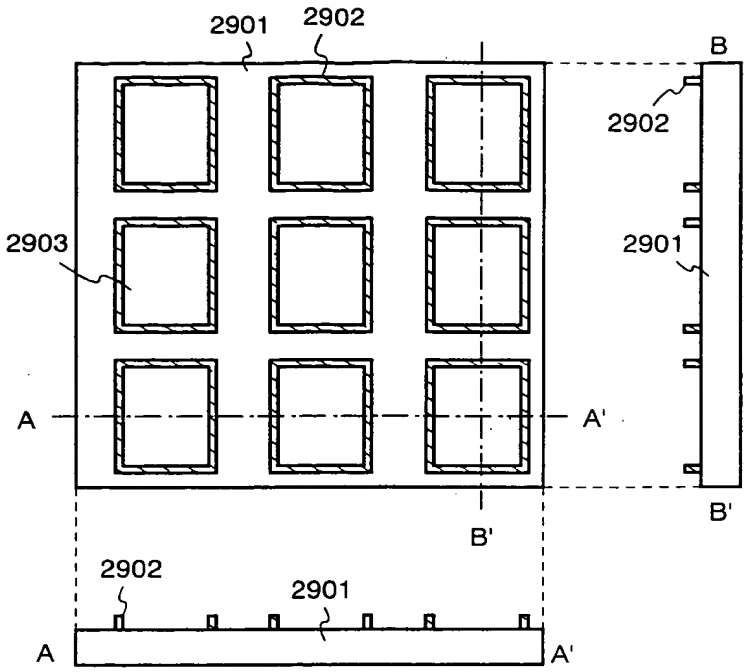


Fig.21B

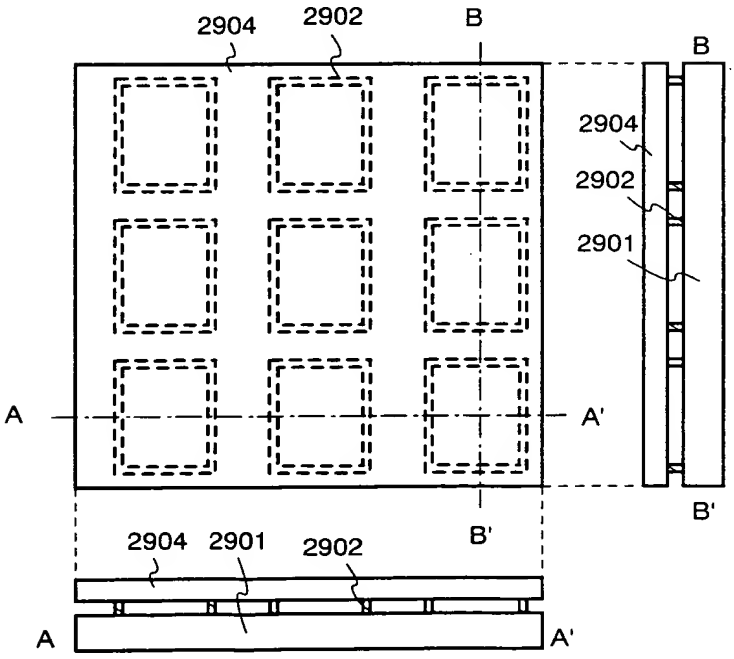


Fig.22A

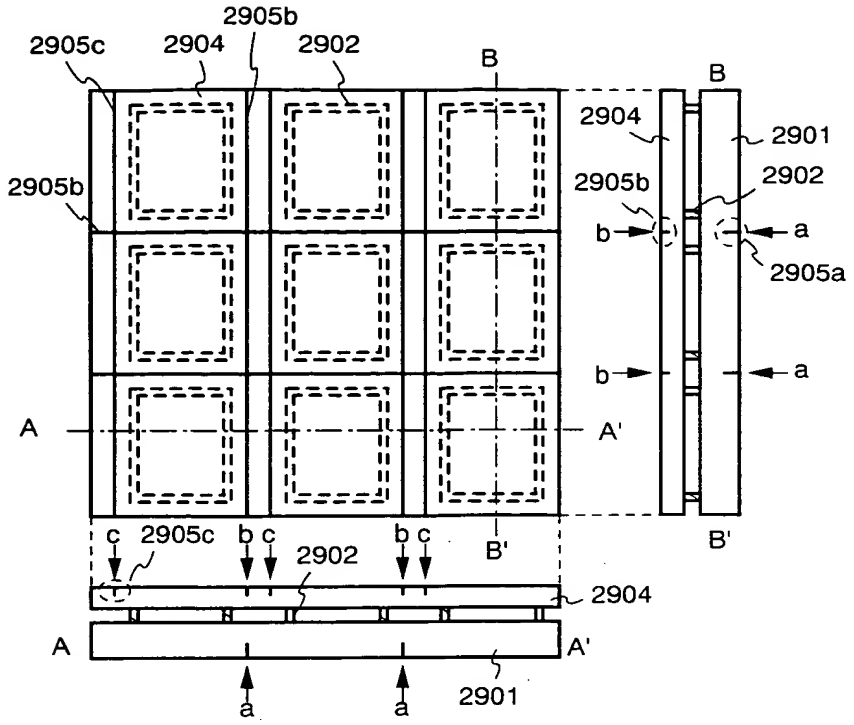
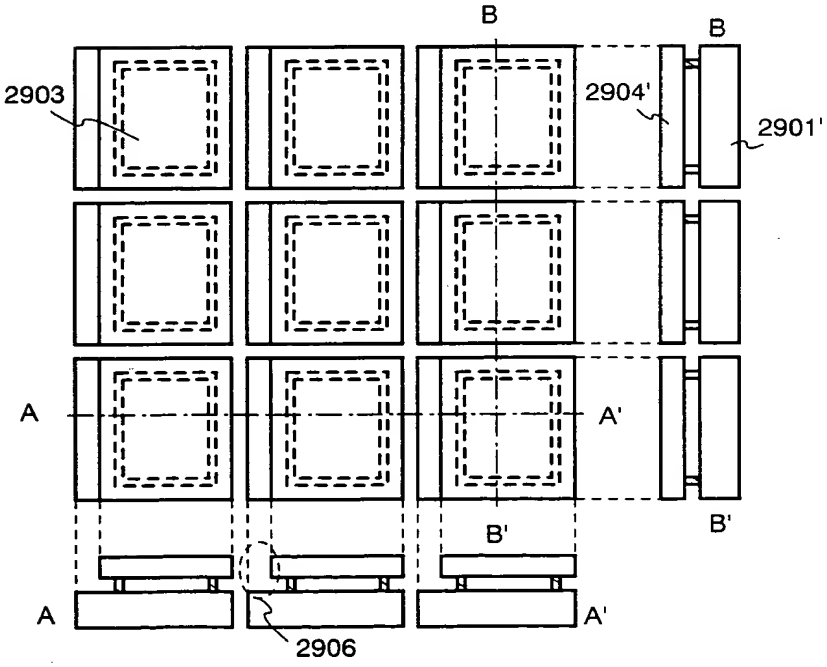


Fig.22B



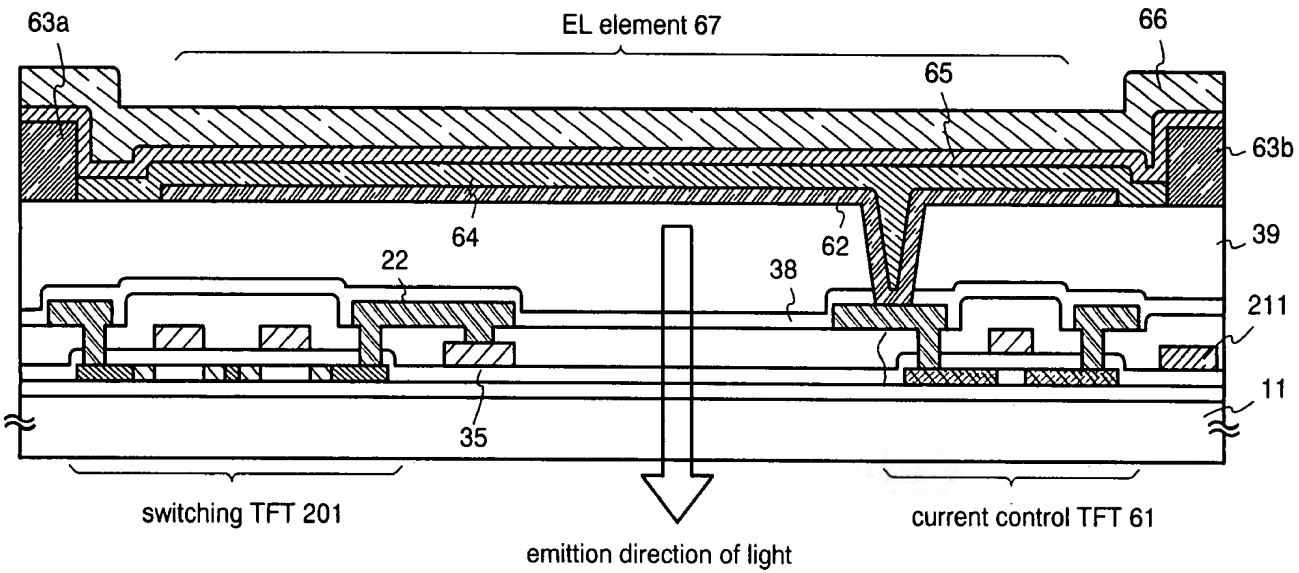

63a
EL element 67
66
65
63b
64
62
39
22
38
211
11
35
switching TFT 201
current control TFT 61
emittion direction of light

Fig.23

Fig.24A

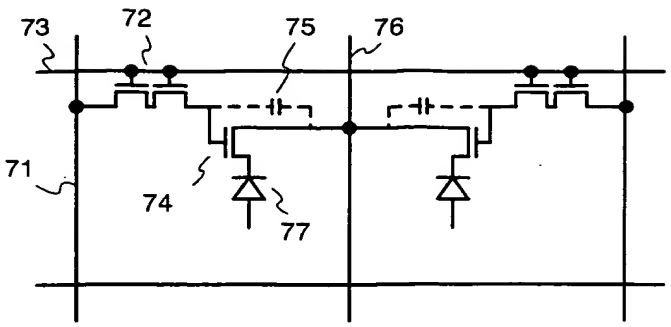


Fig.24B

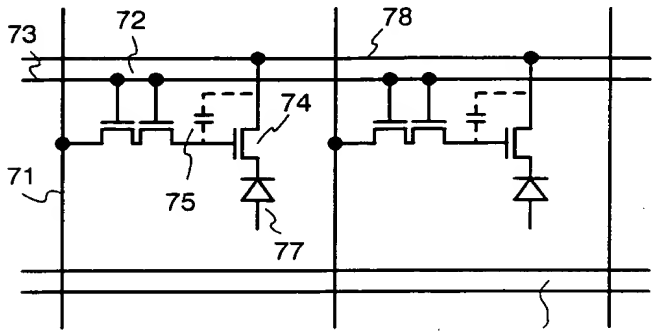


Fig.24C

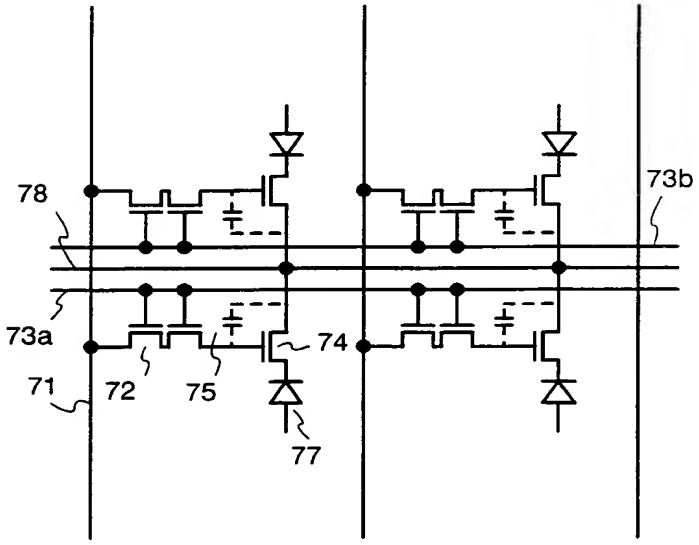


Fig.25A

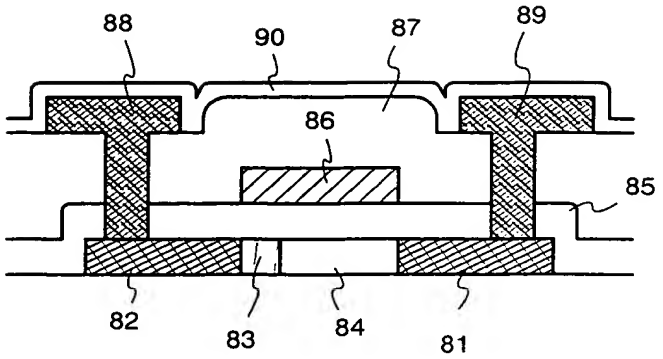


Fig.25B